Radiation Evaluation of Samsung 8 Gbit Flash Memories for Space Application

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Flash versus SDRAM

Flash Features:

+ Non-volatile

R-Write

- + High capacity, 8 Gbit per die
- Slow access to pages
- Wear Out after $> 10^5$ writes / block

SDRAM Features:

- Volatile
- 2 Gbit per die
- + Fast access to bytes
- + No Wear Out



Word Group of 16 Data Bytes + 2 Parity Bytes for Reed-Solomon Single Symbol EC

The storage array of mass memory modules is composed of e.g. 8 Word Groups (WG) of e.g. 16+2 devices, each. Reed Solomon Single Byte Error Correction is capable to correct one faulty byte (= device) out of (16+2) bytes.





Relevance of Device Errors in Case of Single Symbol EC

Type of Device Error / Failure:	Spoiled Data Words:
\geq 2 single bytes of the same Word	1
1 page $+$ n bytes of the same WG Page	n
1 column + n bytes of the same WG Column	n
1 block + n bytes of the same WG Block	n
1 device + n bytes of the same WG	n
1 page + n pages of the same WG Page	4k
1 page + n columns of the same WG	n
• • •	
1 device + n bytes of the same WG	n
1 device + n pages of the same WG	$n \cdot 4k$
1 device + n columns of the same WG	n · 64
1 device + n blocks of the same WG	$n \cdot 4k \cdot 64$
1 device + n devices of the same WG	$\mathbf{n} \cdot 4\mathbf{k} \cdot 64 \cdot 4\mathbf{k} = 1\mathbf{G}$

Typically "Flash Write" fails before "Flash Read".

Data of "no more writable" devices still can be retrieved and swapped to other memory locations.

Classification of device errors and error class individual cross sections are needed to predict the memory performance in space (e.g. BER).



Basic Cell Operation, Basic Cell Error Mechanisms, NAND Flash Structure





Functional Block Diagram of 8 Gbit NAND Flash Memory Devices





Basic Flash Memory Operations

Program: Pagewise

Serial byte transfer user \rightarrow 4224 byte data register DR, parallel programming of "0" by pulsed electron tunneling, page program time:

4224 byte \cdot 30 ns/byte + < 700 µs \approx < 850 µs

Read: Pagewise Status of $4224 \cdot 8$ selected transistors \rightarrow DR, serial byte transfer DR \rightarrow user, page read time:

4224 byte \cdot 30 ns/byte + 25 μ s \approx 150 μ s

Erase: Blockwise \rightarrow "1" Parallel discharging of 4224 \cdot 8 \cdot 64 storage cells by pulsed electron tunneling, block erase time: < 2 ms



Device internal voltage generator delivers "high voltage" pulses of about 20 V to achieve sufficient electrical field strength ($\approx 20 \text{ MeV/cm}$) across the thin oxide (< 10 nm) between channel and floating gate for program / erase tunneling.

Flash operation requires many clock cycles and command executions like the operation of internal state machines, data and command registers, high voltage generators, a.s.o.

- $\Rightarrow \qquad \text{Numerous potential error types} \\ \text{besides the corruption of the content of storage cells.}$
- \Rightarrow Classification of **observed** errors needed.



Error Classification Scheme





Heavy Ion Induced Single Errors (Class A)



*: Open Symbols indicate "no errors up to this cross-section"



Heavy Ion Induced SEFIs (Class B+C)





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Heavy Ion Induced Destructive Failures of the Samsung 8 Gbit NAND Flash

- a) SELs have not been observed up to Xe (LET = $60 \text{ MeV cm}^2 \text{ mg}^{-1}$)
- b) Other Destructive Failures (DF) have been observed only in test modes, which include erase and program operations.
 Biased DUTs, during the irradiation non-accessed or only read-accessed, did not show any DFs.
- c) Power cycling after each erase improves the DF cross section substantially. Using this countermeasure the threshold LET is situated between Fe (LET = 18) and Kr (LET = 32).
- d) The program current grows in steps with the fluence, until it reaches a characteristic final waveform, which soon is followed by a DF.
- e) The waveform of the program current changes from page to page.

From d) and e) we conclude that the observed DFs were caused by accumulation of ion induced defects, which at least in part did anneal during the irradiation.

Faroukh Irom and others reported a thermal destruction of the high voltage generator, which they could avoid by shielding its area.

In contrast e) suggests that the over-current stress of the high voltage generator originates from an accumulation of leakage points within the cell array.



Development of the Program Current until DF Occurrence



Initial

Increase with fluence

Final



Wear Out Limit not degraded by Co-60 TID



No degrading of the wear out limit with dose

Number of Erase-Program-Cycles n_{EPC} until Wear Out, Samsung 8 Gbit, 4 DUTs



TID induced Single Errors

DUTs not accessed during Co-60 γ -irradiation show the first Single Errors at about 40 krad at ambient temperature, and at about 30 krad for DUTs at 85°C.



Biased Storage Mode, 135 rad min⁻¹, 25°C

Biased Storage Mode, 135 rad min⁻¹, 85°C



TID induced Single Errors

DUTs refreshed every 5 krad show the first Single Errors between 100 krad and more than 160 krad at ambient temperature.



Biased Storage Mode, 5 krad Refresh

*: Open Symbols indicate "no errors up to this dose"



TID induced increase of the Standby Current



Biased Storage Mode, 135 rad min⁻¹, 25°C

Biased Storage Mode, 135 rad min⁻¹, 85°C



Issues to be studied further

Heavy Ions, Protons, TID:

- Survey of newcomers on the market (Micron 8 Gbit,).
- Temperature dependence of SEE and TID test data (cross section, standby current).

Heavy lons:

- Destructive Failures
 - a) Cross Section curve of 8 Gbit NAND-Flash Test data of more DUTs are needed.
 - b) Upgrade of the test bed for automatic recording of read, program and erase current waveforms of selected pages / blocks, and performing of respective tests.
 - c) Test of potential countermeasures against Destructive Failures.
 - d) Flux dependence of cross sections
- Omni directional particle incidence in space, High LET ion tests with tilting around two orthogonal axes.

TID:

- Effect of Erase after 10 krad, 20 krad, 40 krad?
- Test at intermediate temperatures, e.g. 40°C, 60°C, 75°C ?
- Time consuming tests at lower dose rate, e.g. 1 rad min⁻¹, 0.1 rad min⁻¹.

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